



東北大学

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## **Electric field control of two-dimensional electrons in polymer-gated oxide semiconductor heterostructures**

The research group of Prof. Kawasaki in WPI-AIMR has successfully demonstrated the systematic control of two-dimensional (2D) electron transport at oxide heterointerfaces using Schottky-gating via conducting polymer, PEDOT:PSS (poly(3,4-ethylenedioxythiophene):poly(styrenesulfonate)). PEDOT:PSS works excellent Schottky contact electrode on oxide semiconductor ZnO because of clean organic-inorganic interface with abruptness both in crystallographic and electronic properties. In this study, a field-effect transistor shown in Fig. 1 was fabricated by conventional molecular-beam epitaxy for MgZnO/ZnO heterostructures and spin coating for PEDOT:PSS. 2D electron density and conductivity were systematically tuned by the application of gate bias voltage at 2 K. In addition, we found interesting physical phenomenon of insulator-to-metal transition at a certain gate bias as shown in Fig. 3. These achievements pave a way for harmless, transparent, and low cost field-effect transistors. This work was performed for a sample supplied from ROHM Co. Ltd. These results will be published in *Advanced Materials* at November 25<sup>th</sup>, 2009.

### **<Title and authors>**

“Electric field control of two-dimensional electrons in polymer-gated oxide semiconductor heterostructures”

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*Advanced Materials*, in press.

[Contact about the research]

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< Figures >

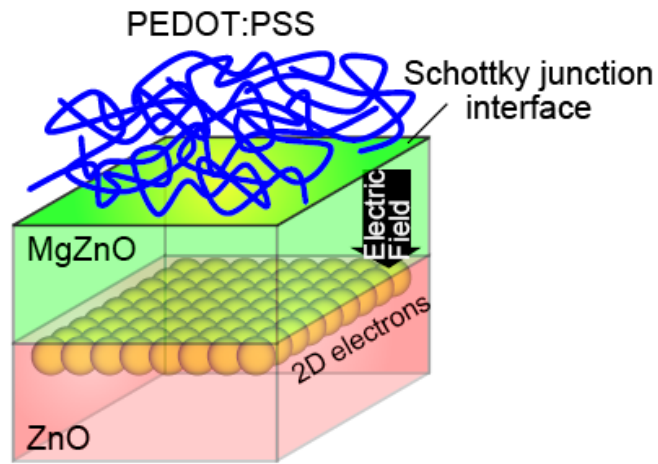


Fig. 1 Simple cross-sectional illustration of the field-effect transistor device.

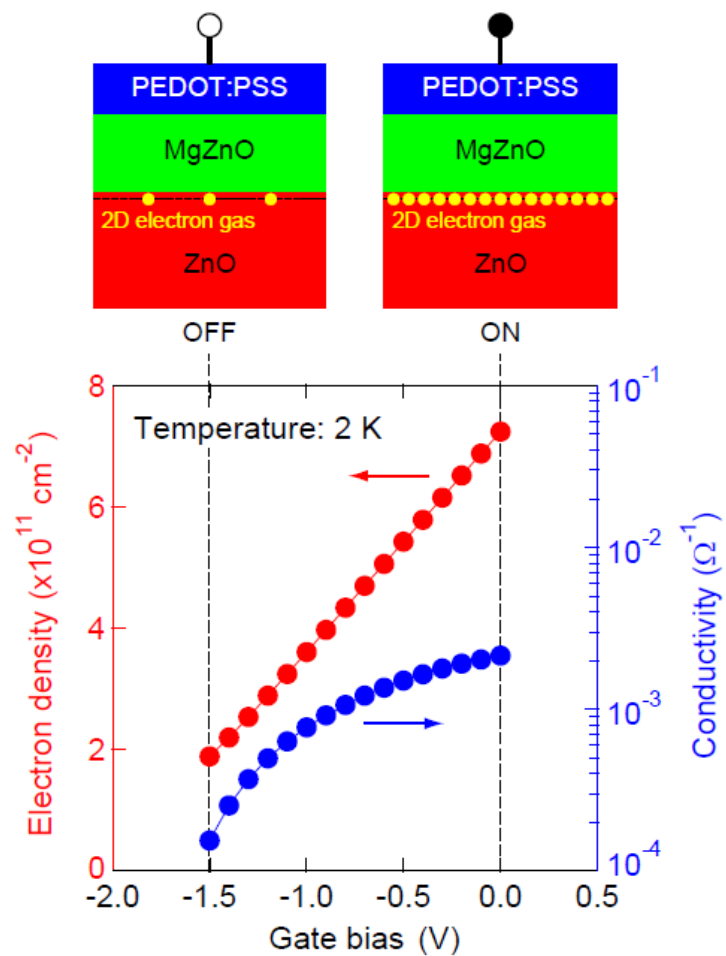


Fig. 2 Electron density and conductivity as a function of gate bias.

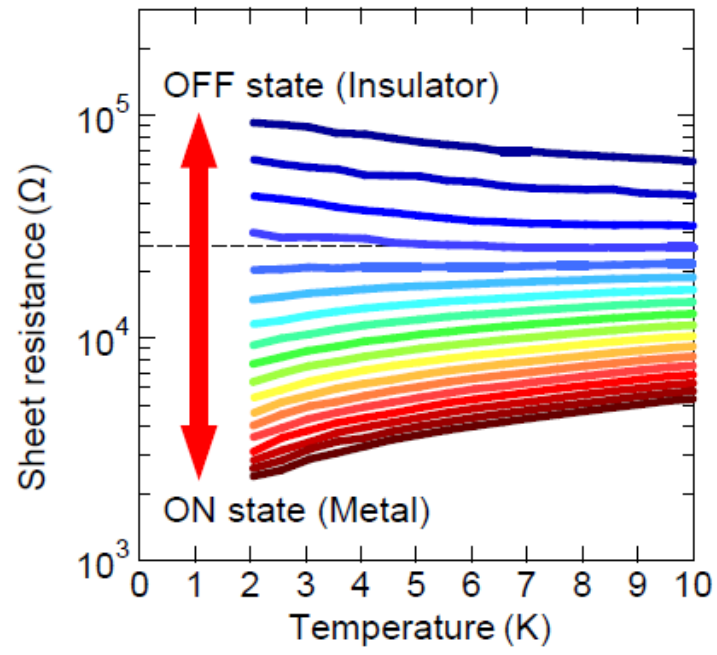


Fig. 3 Insulator-to-metal transition tuned by gate bias voltage.